

Docket No.: 006217 USA/Consilium/Consilium

PATENT/OFFICIAL

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Re Application of :
: Nicholas A. WARD et al. :
: Serial No. 09/927,444 : Group Art Unit: 2125
: Filed: August 13, 2001 : Examiner: Sean P. Shechtman

For: DYNAMIC CONTROL OF WAFER PROCESSING PATHS IN SEMICONDUCTOR
MANUFACTURING PROCESSES

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Honorable Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In accordance with the provisions of 37 C.F.R. 1.56, 1.97 and 1.98, the attention of the Patent and Trademark Office is hereby directed to the documents listed on the attached form PTO-1449. It is respectfully requested that the documents be expressly considered during the prosecution of this application, and that the documents be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed after a Request for Continued Examination, before the mailing date of a first Office Action on the merits or Notice of Allowance. No certification or fee is required.

This submission does not constitute a representation that a search has been made or that no better art exists and does not constitute an admission or representation that any of the listed


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documents is material or constitutes prior art. If it should be determined that any of the listed documents does not constitute prior art under the United States law, Applicants reserve the right to present to the Office the relevant facts and law regarding the appropriate status of such document.

No fee is believed to be required, however, the Commissioner is hereby authorized to charge any additional fees that may be required for this submission, or credit any overpayment to deposit account no. 08-0219.

Respectfully submitted,


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INFORMATION DISCLOSURE CITATION IN AN APPLICATION 				ATTY. DOCKET NO. 006217 USA/ Consilium/Consilium		SERIAL NO. 09/927,444	
				APPLICANT Nicholas A. WARD et al.			
				FILING DATE August 13, 2001		GROUP 2125	
U.S. PATENT DOCUMENTS							
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE	
	6,230,069 B1	05/08/01	Campbell et al.			06/26/98	
	6,268,270 B1	07/31/01	Scheid et al.			10/29/99	
	6,291,367 B1	09/18/01	Kelkar			06/01/00	
	6,465,263 B1	10/15/02	Coss, Jr. et al.			01/04/00	
	6,532,555 B1	03/11/03	Miller et al.			10/29/99	
	6,535,783 B1	03/18/03	Miller et al.			03/05/01	
	6,541,401 B1	04/01/03	Herner et al.			07/31/00	
	6,546,508 B1	04/08/03	Sonderman et al.			10/29/99	
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	6,652,355 B2	11/25/03	Wiswesser et al.			06/04/01	
	6,725,402 B1	04/20/04	Coss, Jr. et al.			07/31/00	
EXAMINER				DATE CONSIDERED			

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

<p align="center">INFORMATION DISCLOSURE CITATION IN AN APPLICATION</p> <p align="center">(PTO-1449)</p>	<p>ATTY. DOCKET NO. 006217 USA/ Consilium/Consilium</p>	<p>SERIAL NO. 09/927,444</p>
	<p>APPLICANT Nicholas A. WARD et al.</p>	
	<p>FILING DATE August 13, 2001</p>	<p>GROUP 2125</p>
<p align="center">OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)</p>		
	<p>IslamRaja, M. M., C. Chang, J. P. McVittie, M. A. Cappelli, and K. C. Saraswat. May/June 1993. "Two Precursor Model for Low-Pressure Chemical Vapor Deposition of Silicon Dioxide from Tetraethylorthosilicate." <i>J. Vac. Sci. Technol. B</i>, Vol. 11, No. 3, pp. 720-726.</p>	
	<p>Kim, Eui Jung and William N. Gill. July 1994. "Analytical Model for Chemical Vapor Deposition of SiO₂ Films Using Tetraethoxysilane and Ozone" (Abstract). <i>Journal of Crystal Growth</i>, Vol. 140, Issues 3-4, pp. 315-326.</p>	
	<p>Guo, R.S, A. Chen, C.L. Tseng, I.K. Fong, A. Yang, C.L. Lee, C.H. Wu, S. Lin, S.J. Huang, Y.C. Lee, S.G. Chang, and M.Y. Lee. June 16-17, 1998. "A Real-Time Equipment Monitoring and Fault Detection System." <i>Semiconductor Manufacturing Technology Workshop</i>, pp. 111-121.</p>	
	<p>Lantz, Mikkell. 1999. "Equipment and APC Integration at AMD with Workstream." <i>IEEE</i>, pp. 325-327.</p>	
	<p>July 15, 2004. Office Action for U.S. Serial No. 10/172,977, filed June 18, 2002.</p>	
	<p>August 2, 2004. Office Action for U.S. Serial No. 10/174,377, filed June 18, 2002.</p>	
	<p>August 9, 2004. Written Opinion for PCT Serial No. PCT/US02/19063.</p>	
	<p>August 18, 2004. International Preliminary Examination Report for PCT Serial No. PCT/US02/19116.</p>	
	<p>August 24, 2004. Office Action for U.S. Serial No. 10/135,405, filed May 1, 2002.</p>	
	<p>August 25, 2004. Office Action for U.S. Serial No. 09/998,384, filed November 30, 2001.</p>	
	<p>September 9, 2004. Written Opinion for PCT Serial No. PCT/US02/21942.</p>	
	<p>September 16, 2004. International Preliminary Examination Report for PCT Serial No. PCT/US02/24859.</p>	
EXAMINER	DATE CONSIDERED	

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